

## IV. Detector Systems – Conflicts and Compromises

### Conflicts

Custom integrated circuits essential for vertex detectors in HEP.

### Requirements

1. low mass to reduce scattering
2. low noise
3. fast response
4. low power
5. radiation tolerance

reduction in mass  $\Rightarrow$  thin detector

radiation tolerance  $\Rightarrow$  thin detector

thin detector  $\Rightarrow$  less signal  $\Rightarrow$  lower noise required

lower noise  $\Rightarrow$  increased power

fast response  $\Rightarrow$  increased power

increased power  $\Rightarrow$  more mass in cabling + cooling

immunity to external pickup  $\Rightarrow$  shielding  $\Rightarrow$  mass

+ contain costs

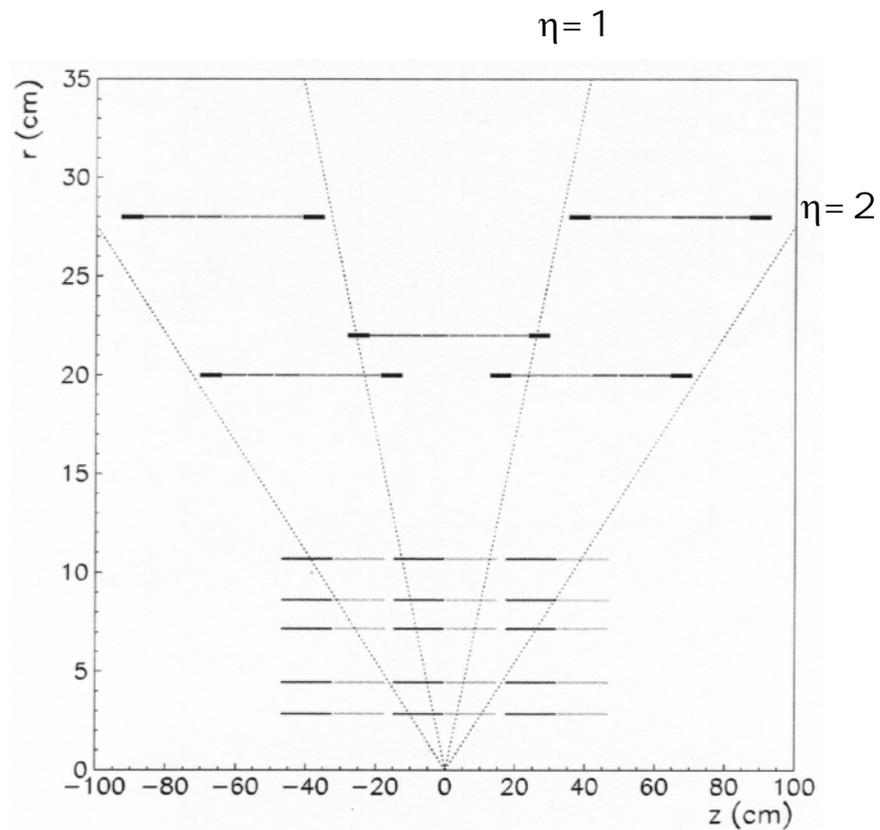
How to deal with these conflicting requirements?

Some examples ...

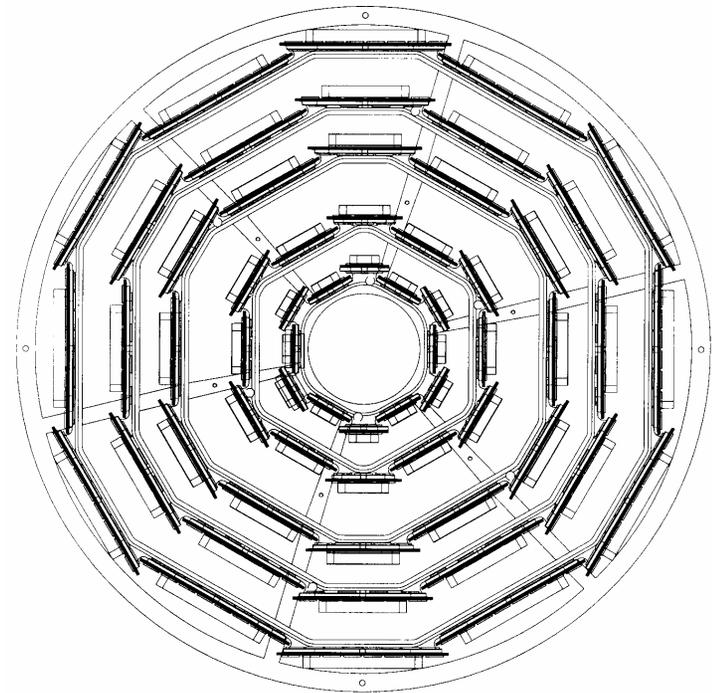
## 2. CDF Vertex Detector Upgrade: SVX2

Expand coverage of existing vertex detector

a) side view ( $z = \text{beam axis}$ )



b) axial view of vertex detector



Property	Layer 0	Layer 1	Layer 2	Layer 3	Layer 4
Radial distance (cm)	2.45	4.67	7.02	8.72	10.6
Stereo angle (degrees)	90	90	+1.2	90	-1.2
$r\phi/z$ readout channels	256/512	384/576	640/640	768/512	896/896
$r\phi/z$ readout chips	2/2	3/3	5/5	6/4	7/7
$r\phi/z$ strip pitch ( $\mu\text{m}$ )	60/141	62/125.5	60/60	60/141	65/65
Total width (mm)	17.14	25.59	40.30	47.86	60.17
Total length (mm)	74.3	74.3	74.3	74.3	74.3

Layers 0, 1 and 3 use 90° stereo angle, whereas layers 4 and 5 use 1.2° stereo angle to reduce ghosting.

## Electronic Readout

SVX2 uses the SVX3 chip, which is a further development of the SVX2 chip used by DØ.

Include on-chip digitization of analog signal

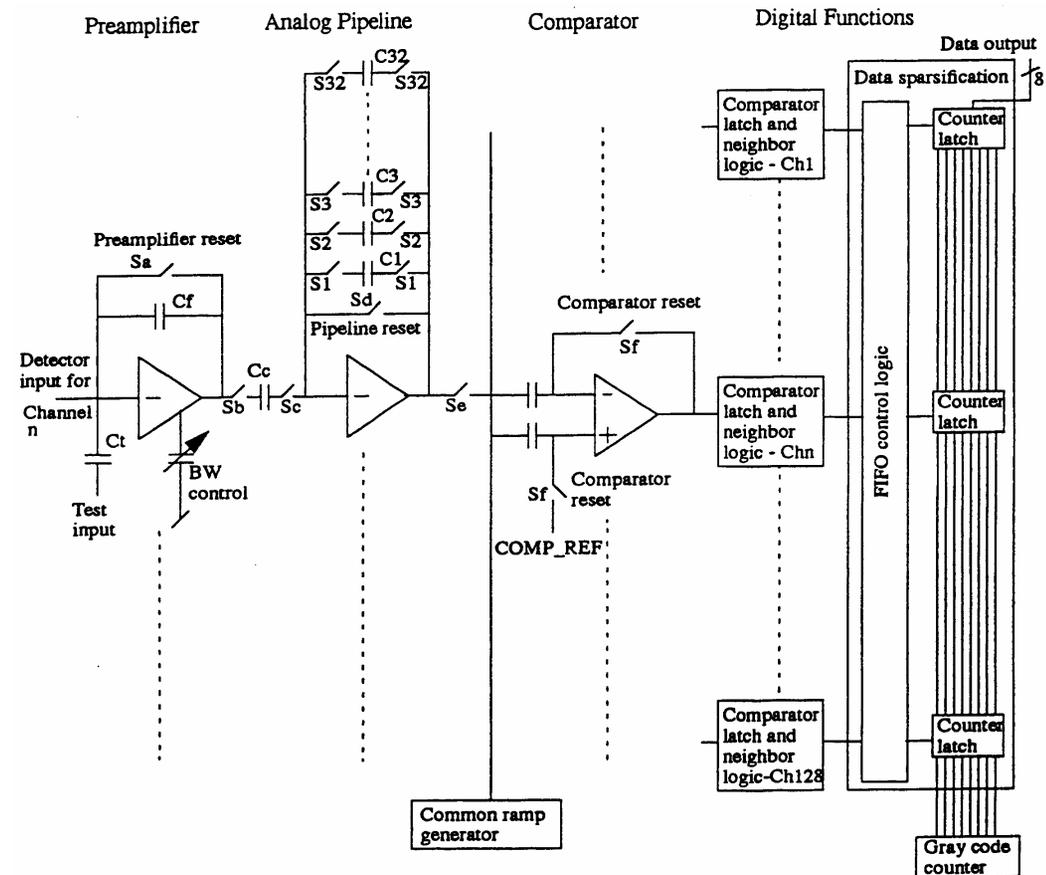
Threshold, calibration via on-chip DACs

All communication to and from chip via digital bus

Wilkinson ADC integrated with pipeline + comparator, which is also used for sparsification. Adds 100  $\mu\text{m}$  to length and 300  $\mu\text{W}/\text{ch}$  power.

ADC clock runs at 106 MHz in experiment, tested to 400 MHz

Total power: 3 mW/ch



## SVX2 die layout

Dimensions: 6.3 x 8.7 mm 0.8  $\mu\text{m}$ , triple-metal rad-hard CMOS

Input Pads

Preamplifiers

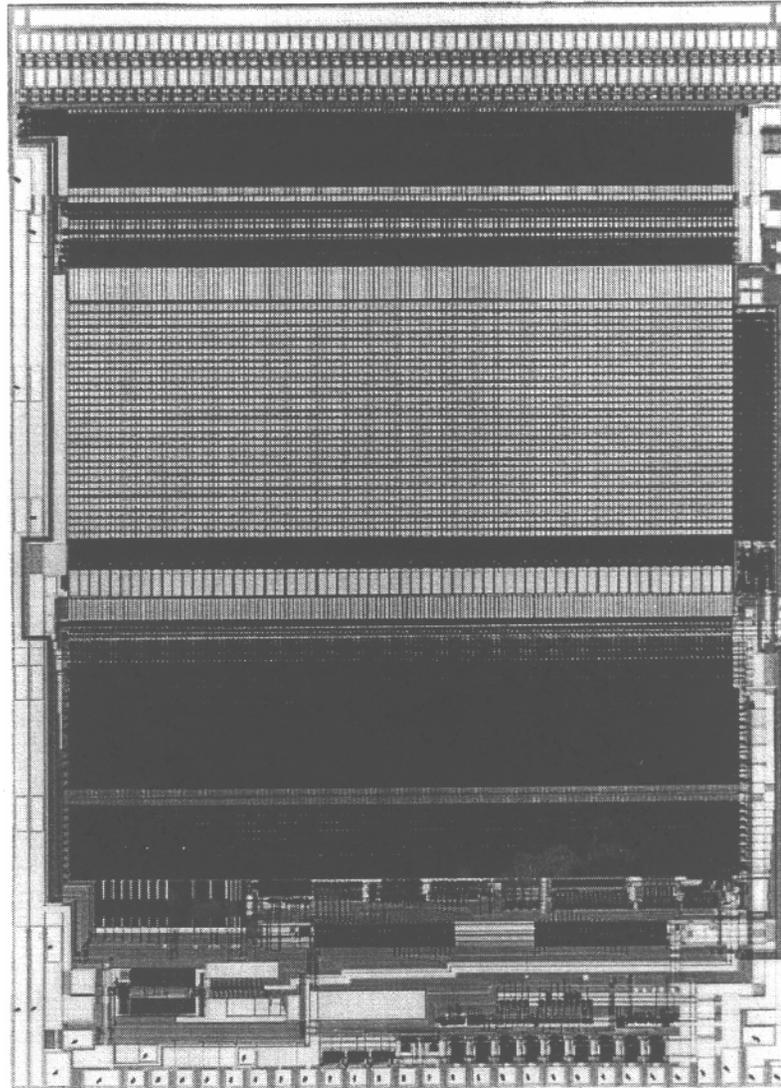
Analog Pipeline

ADC Comparator

Neighbor Logic

Sparsification +  
Readout

ADC Ramp +  
Counter, I/O



SVX2 (used by DØ) is designed for sequential signal acquisition and readout.

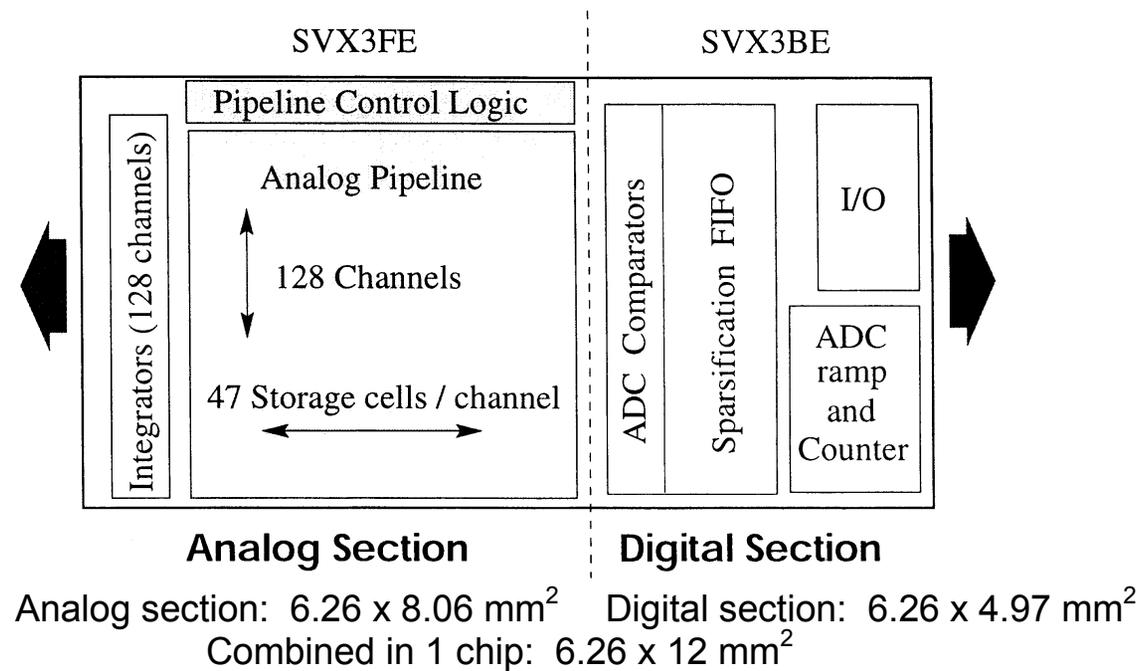
SVX3 (used by CDF) allows concurrent read-write, i.e. signal acquisition and readout can proceed concurrently.

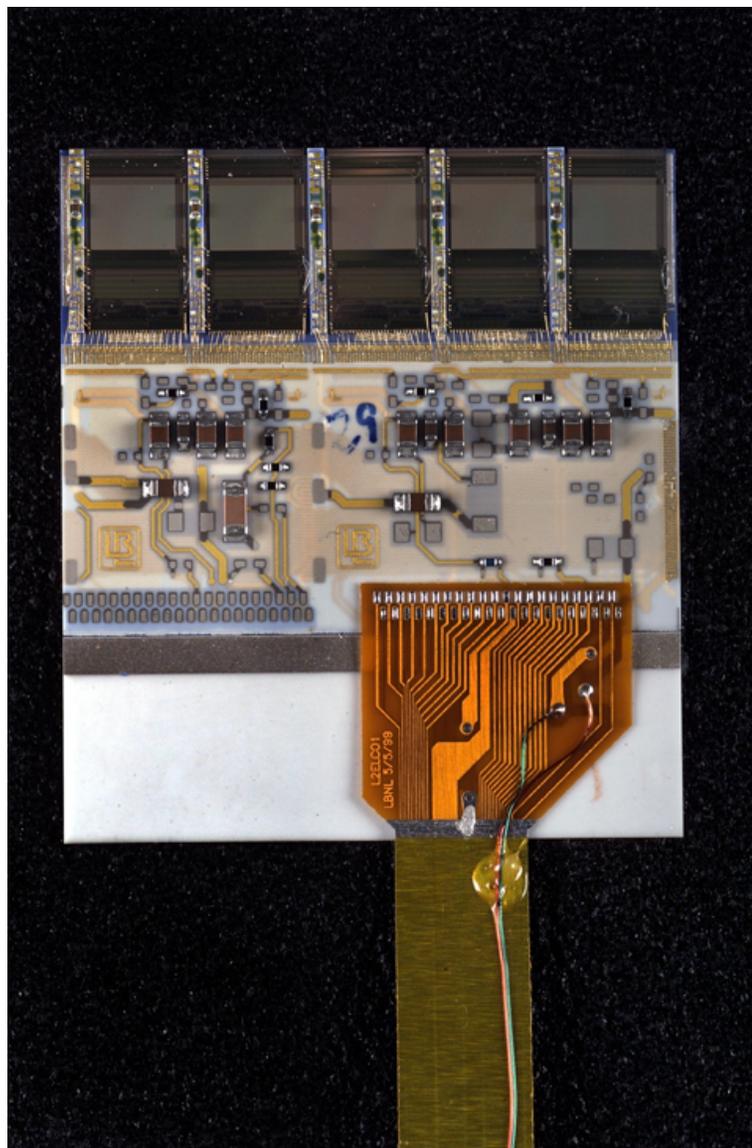
### SVX3 Floor Plan

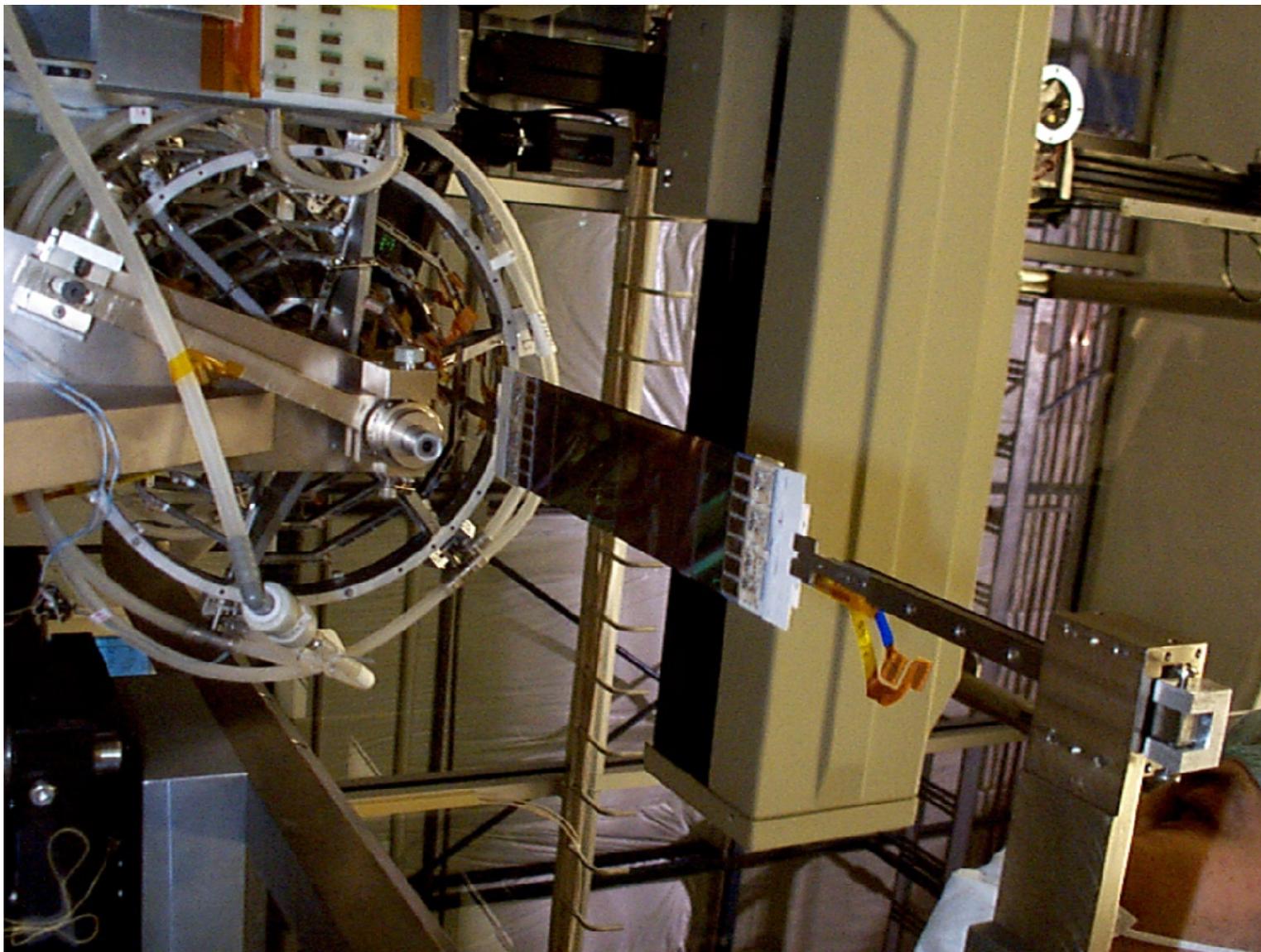
Measured Noise:

$$Q_n = 500 \text{ el} + 60 \text{ el/pF rms}$$

Both chips fabricated in rad-hard CMOS.







*Front-End Electronics and Signal Processing – IV. Systems  
2003 ICFA Instrumentation School, Itacuruçá, Brazil*

*Helmuth Spieler  
LBNL*

SVX2 and SVX3 utilize correlated double sampling for pulse shaping

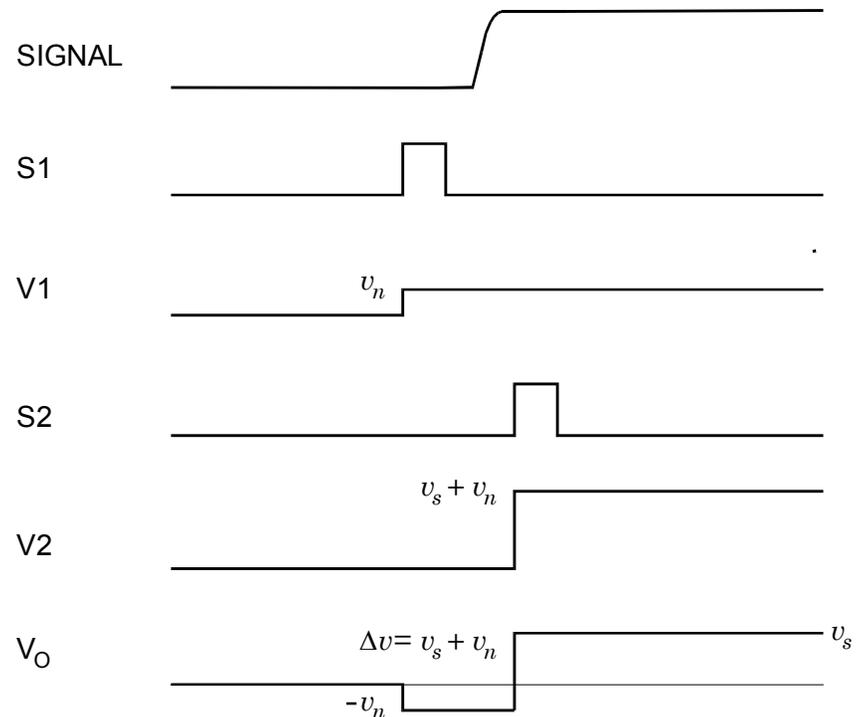
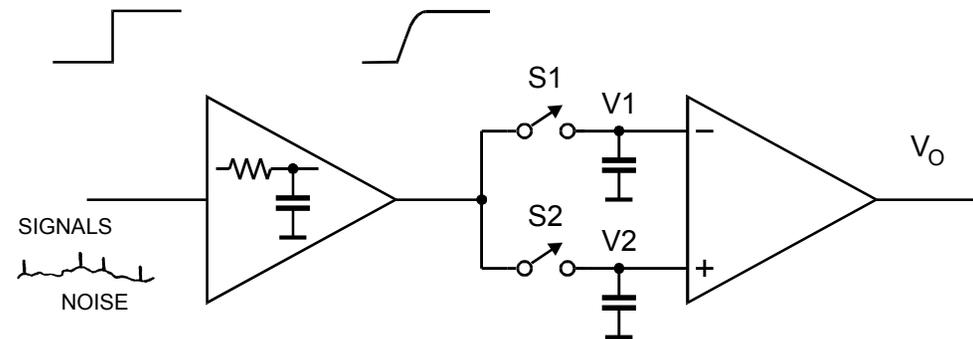
(see Signal Processing 1)

Correlated double sampling requires prior knowledge of signal arrival.

OK for colliders if  $\Delta T_{beam} > T_{shaper}$ , but not for random signals.

High luminosity colliders (B Factories, LHC) have much shorter beam crossing intervals

⇒ continuous shaping required



### 3. BaBar Silicon Vertex Tracker

$B$  mesons from  $\Upsilon(4S)$  production have low momentum.

Asymmetry in beam energies (9 GeV  $e^-$  on 3.1 GeV  $e^+$ ) used to provide boost ( $\beta\gamma = 0.56$ ) that allows conventional vertex detectors to cope with short  $B$  meson lifetime.

Vertex detector must provide resolution in boost direction, i.e. parallel to beam axis, rather than in  $r\phi$ .

Resolution requirement not stringent:

Less than 10% loss in precision in the asymmetry measurement if the separation of the B vertices is measured with a resolution of  $\frac{1}{2}$  the mean separation (250  $\mu\text{m}$  at PEP-II)

$\Rightarrow$  80  $\mu\text{m}$  vertex resolution required for both CP eigenstates and tagging final states.

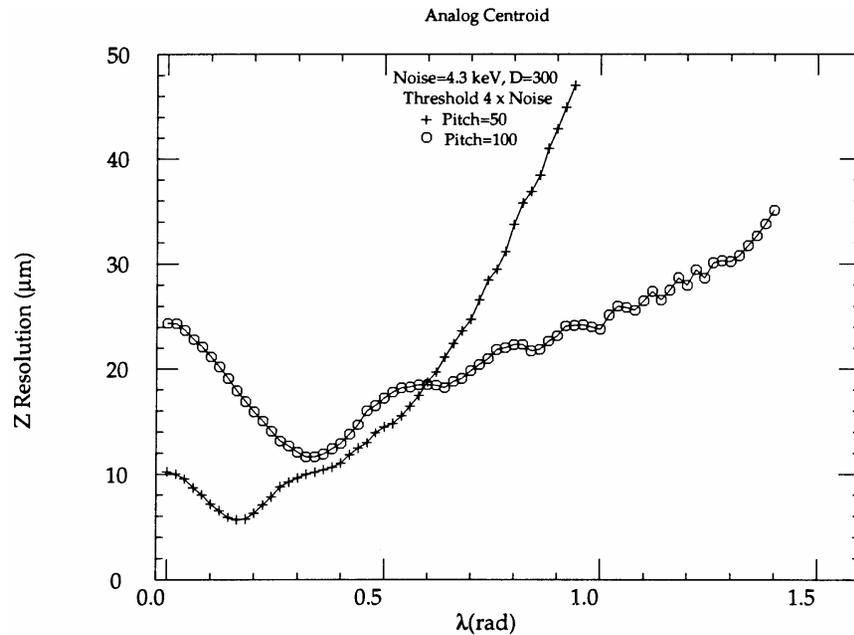
Resolution is multiple-scattering limited:      beam pipe: 0.6%  $X_0$

Use crossed strips:       $z$ -strips for vertex resolution  
                                   $r\phi$  strips for pattern recognition

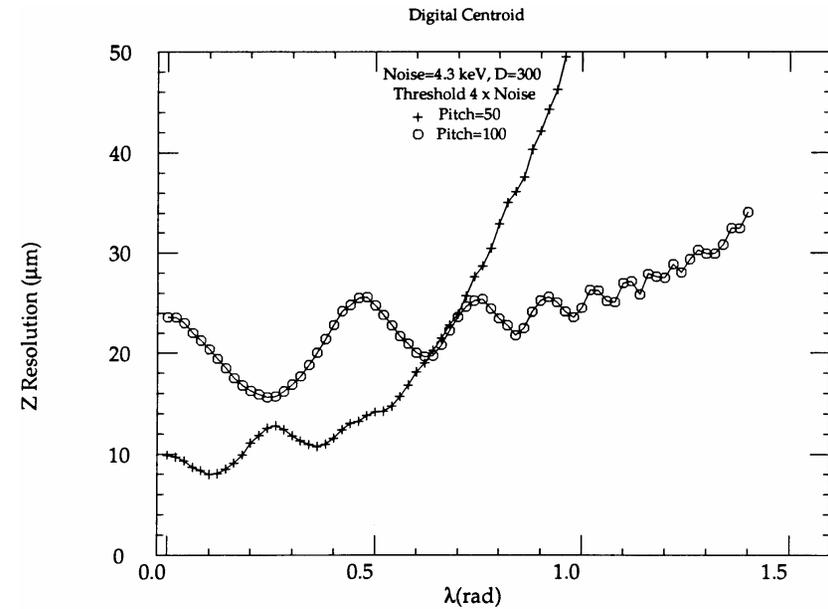
Measurement does not require utmost position resolution       $\Rightarrow$       use binary readout

Position resolution for analog and binary readout vs dip angle  $\lambda$ .

Analog readout (50 and 100  $\mu\text{m}$  pitch)



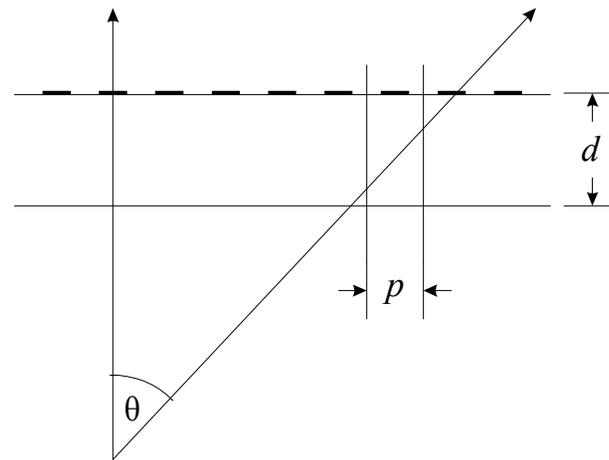
Binary readout (50 and 100  $\mu\text{m}$  pitch)



Why does 100  $\mu\text{m}$  pitch yield better resolution at large dip angles?

Signal in  $z$ -strips degrades at large dip angles

$$Q_s = d \frac{dE}{dx} \qquad Q_s = p \cos \Theta \cdot \frac{dE}{dx}$$



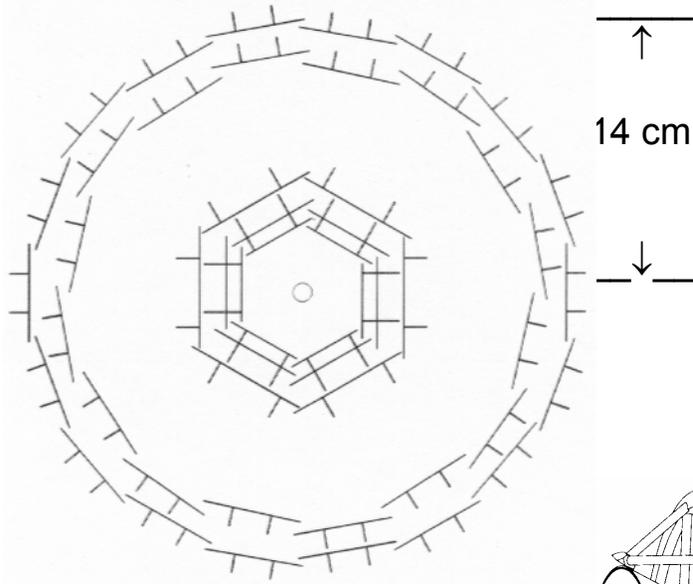
Change strip pitch at  $\lambda > 0.7$  radians

Furthermore ....

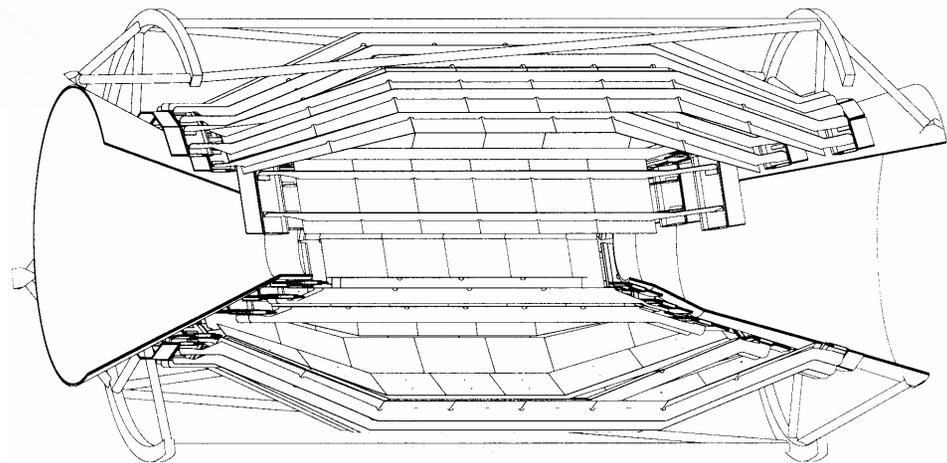
add coarse analog information (3 – 4 bits adequate)

## Mechanical arrangement of detector

Axial view

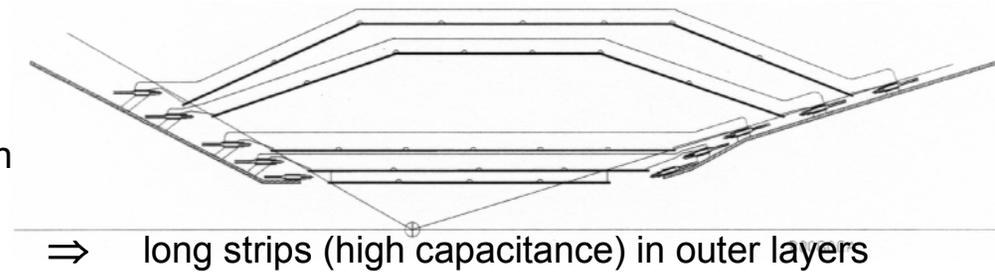


Side view



Outer layers use “lampshade” geometry instead of disks

Electronics mounted outside of active region  
(connected to detectors by kapton cables)



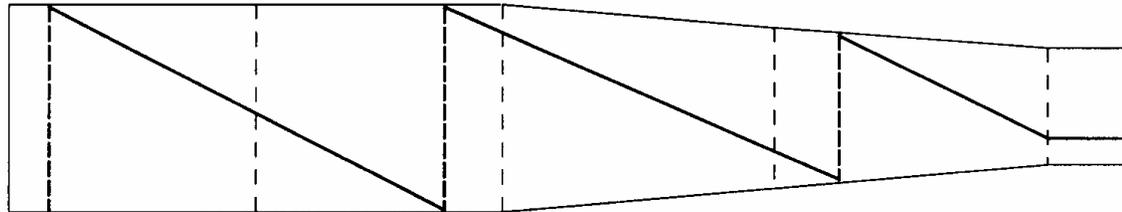
Layer	Fanout Type	Length (cm)	Number of Readout		Typical Pitch at		Number of Circuits
			Strips	Channels	Input ( $\mu\text{m}$ )	Output ( $\mu\text{m}$ )	
1	$z$ , F+B	12.5	950	768	100	50	12
	$\phi$ , F+B	3.0	768	768	50	50	12
2	$z$ , F+B	14.5	1150	1024	100	50	12
	$\phi$ , F+B	3.0	960	1024	50	50	12
3	$z$ , F+B	15.6	1360	1280	100	50	12
	$\phi$ , F+B	2.0	1280	1280	50	50	12
4a	$z$ , F	19.7	885	512	200	50	8
	$z$ , B	24.3	1115	512	200	50	8
	$\phi$ , F+B	2.0	512	512	65	50	16
4b	$z$ , F	20.6	930	512	200	50	8
	$z$ , B	24.2	1160	512	200	50	8
	$\phi$ , F+B	2.0	512	512	65	50	16
5a	$z$ , F	25.2	1160	512	200	50	9
	$z$ , B	25.1	1205	512	200	50	9
	$\phi$ , F+B	2.0	512	512	65	50	18
5b	$z$ , F+B	26.1	1205	512	200	50	18
	$\phi$ , F+B	2.0	512	512	65	50	18

$z$ -strips are connected at ends, to avoid cables in middle of detector.

Kapton connecting cables that connect multiple detector segments  
(use  $r\phi$  resolution to disentangle ambiguities)

Kapton rather than “double metal” to reduce capacitance (+ cost)

Connections made along diagonals:



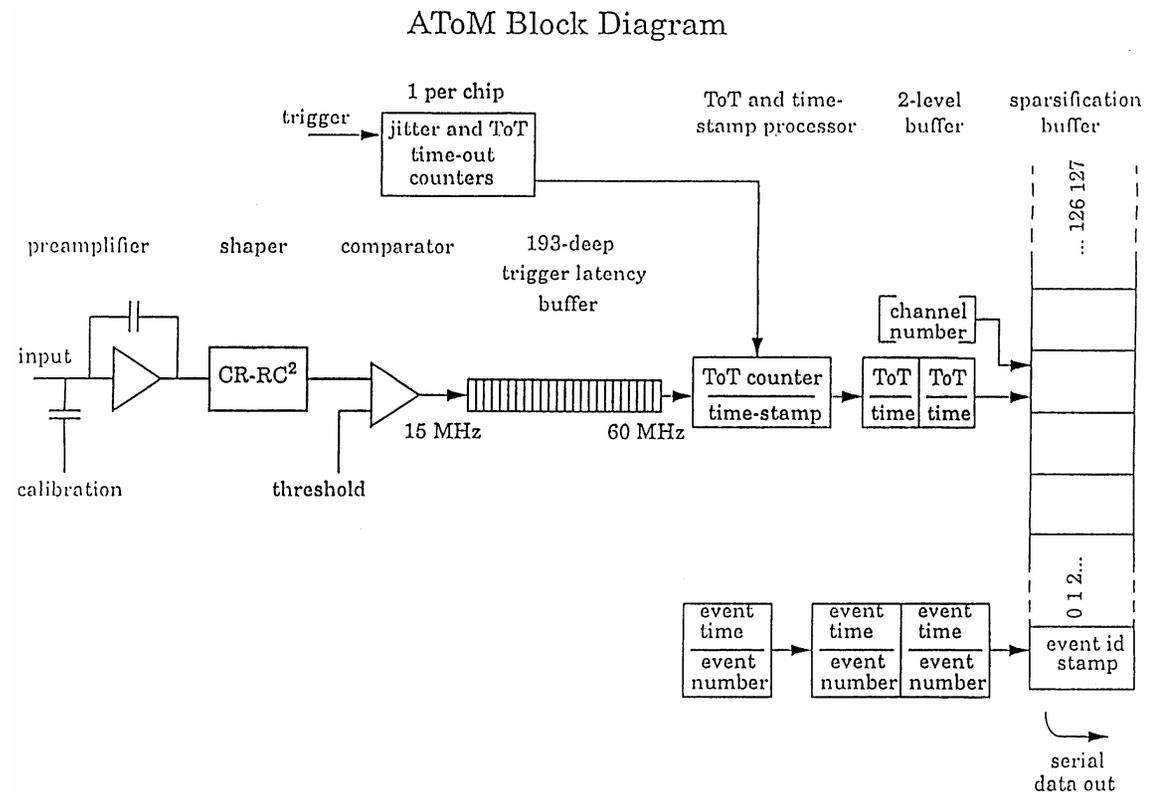
## AToM – Readout IC for BaBar Vertex Detector (LBNL, Pavia, UCSC)

Preamplifier with continuous reset

CR-RC<sup>2</sup> shaper with selectable  
shaping times (100, 200 and 400  
ns)

Outer layers of tracker have  
longer strips (higher  
capacitance) than inner layers.  
Lower occupancy allows use  
of longer shaping time to  
maintain electronic noise.

Coarse digitization via Time-  
Over-Threshold  
(analog information for position  
interpolation only requires 3 – 4  
bit resolution)



Measured noise (pre-production run) for 3 shaping times

100 ns:	$Q_n = 350 \text{ el} + 42 \text{ el/pF}$
200 ns:	$Q_n = 333 \text{ el} + 35 \text{ el/pF}$
400 ns:	$Q_n = 306 \text{ el} + 28 \text{ el/pF}$

## 4. Development of a Tracker Concept at the LHC

ATLAS Tracking detector for the LHC:

Colliding proton beams

7 TeV on 7 TeV (14 TeV center of mass)

Luminosity:  $10^{34} \text{ cm}^{-2}\text{s}^{-1}$

Bunch crossing frequency: 40 MHz

Interactions per bunch crossing: 23

Charged particles per unit of rapidity: 150

$$\Rightarrow \text{hit rate } n' = \frac{2 \cdot 10^9}{r_{\perp}^2} \left[ \text{cm}^{-2}\text{s}^{-1} \right], \quad \text{where } r_{\perp} = \text{distance from beam axis}$$

If the detector subtends  $\pm 2.5$  units of rapidity, the total hit rate in the detector is  $3 \cdot 10^{10} \text{ s}^{-1}$

Hit rate at  $r_{\perp} = 14 \text{ cm}$ :  $\sim 10^7 \text{ cm}^{-2}\text{s}^{-1}$

- Overall detector to include
1. Vertexing for B-tagging
  2. Precision tracking in 2T magnetic field
  3. Calorimetry (EM + hadronic)
  4. Muon detection

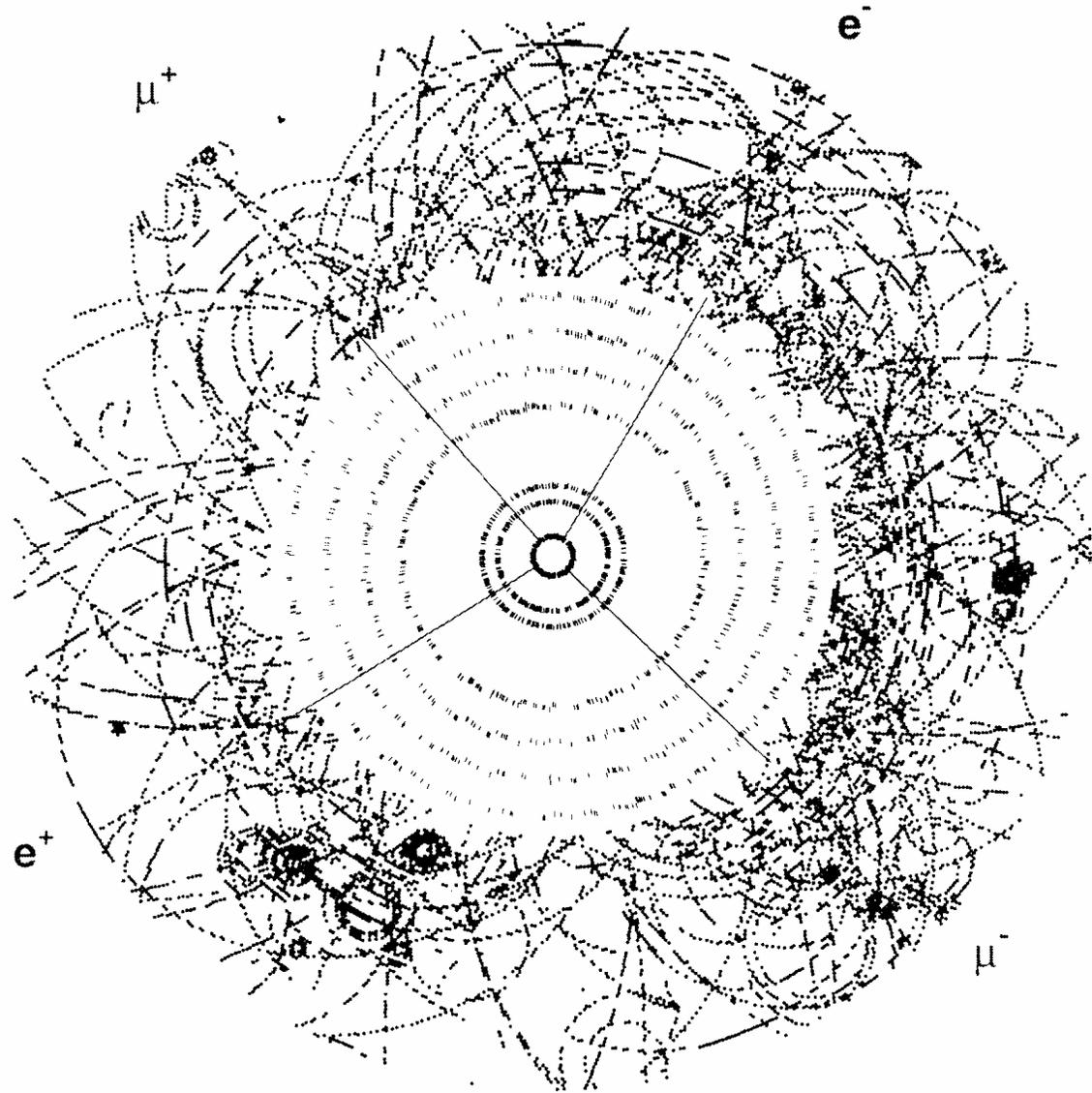
## “Typical Event” – Axial View

$$H \rightarrow ZZ^* \rightarrow \mu^+ \mu^- e^+ e^-$$

( $m_H = 130 \text{ GeV}$ )

Appears worse than it is

– tracks spread azimuthally,  
but high track density at  
forward angles.



## Radiation Damage

Two sources of particles

a) beam collisions

b) neutron albedo from calorimeter

Fluences per year (equivalent 1 MeV neutrons)

$r \sim 10 \text{ cm}$       typ.  $5 \cdot 10^{13} \text{ cm}^{-2}$

$r \sim 30 \text{ cm}$       typ.  $2 \cdot 10^{13} \text{ cm}^{-2}$

Ionizing Dose per year

$r \sim 10 \text{ cm}$       30 kGy (3 Mrad)

$r \sim 30 \text{ cm}$       4 kGy (400 krad)

In reality, complex maps are required of the radiation flux, which is dependent on local material distribution.

How to cope with ...

- High total event rate
  - a) fast electronics
    - high power required for both noise and speed
  - b) segmentation
    - reduce rate per detector element
    - for example, at  $r = 30$  cm the hit rate in an area of  $5 \cdot 10^{-2}$  cm<sup>2</sup> is about  $10^5$  s<sup>-1</sup>, corresponding to an average time between hits of 10  $\mu$ s.
  
- $\Rightarrow$  longer shaping time allowable
- $\Rightarrow$  lower power for given noise level
  
- Large number of events per crossing
  - a) fast electronics (high power)
  - b) segmentation
    - if a detector element is sufficiently small, the probability of two tracks passing through is negligible
  - c) single-bunch timing
    - reduce confusion by assigning hits to specific crossing times
  
- $\Rightarrow$  Segmentation is an efficient tool to cope with high rates.

With careful design, power requirements don't increase.

- ⇒ Fine segmentation feasible with semiconductor detectors
- “ $\mu\text{m}$ -scale” patterning of detectors
  - monolithically integrated electronics mounted locally

Large number of front-end channels requires simple circuitry

Single bunch timing ⇒ collection times  $< 25$  ns

Radiation damage is a critical problem in semiconductor detectors:

- a) detector leakage current  $I_R = I_{R0} + \alpha\Phi Ad$
- ⇒ shot noise  $Q_{ni}^2 = 2q_e I_R F_i T_S$
- ⇒ self-heating of detector  $I_R(T) \propto T^2 e^{-E/2k_B T}$

reduce current by cooling  
 reduce shaping time  
 reduce area of detector element

b) Increase in depletion voltage

- ⇒ thin detector
- ⇒ allow for operation below full depletion
- ⇒ less signal  
 Requires lower noise to maintain minimum S/N
- ⇒ decrease area of detector element (capacitance)

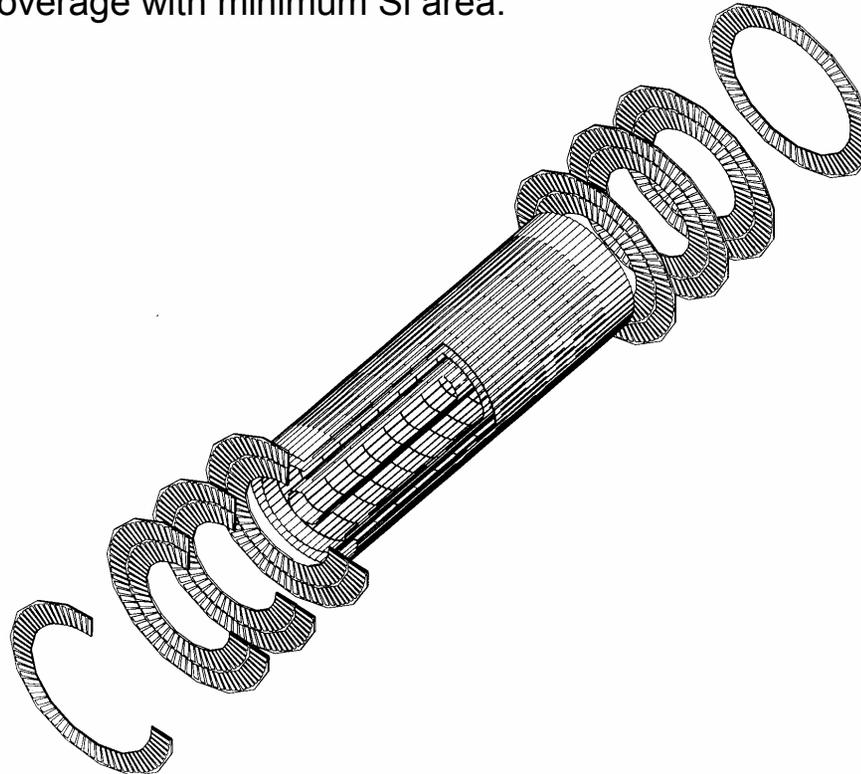
Use of a highly-developed technology, i.e. Si rather than “exotic” materials, provides performance reserves and design flexibility to cope with radiation damage.

## Layout

Full coverage provided by a combination of barrel and disk layers.

- Coverage provided by
- a) barrel in central region
  - b) disks in forward regions

to provide maximum coverage with minimum Si area.



Pixels at small radii (4, 11, 14 cm) to cope with

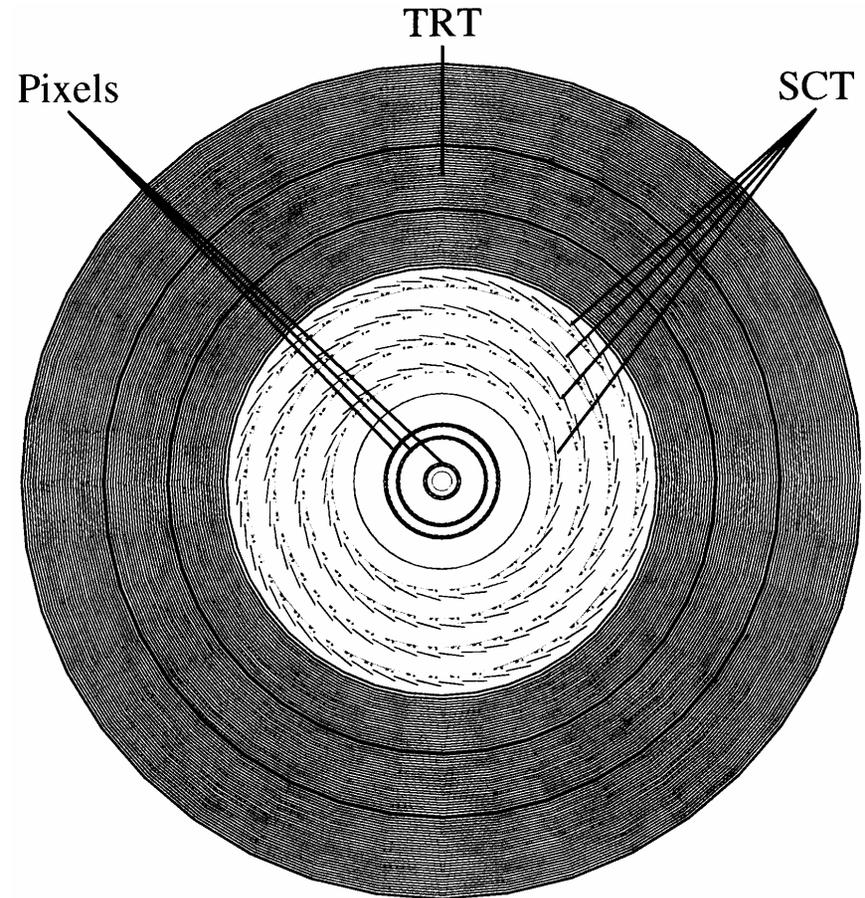
- high event rate (2D non-projective structure)
- radiation damage  
small capacitance  $\sim 100$  fF  
 $\Rightarrow$  low noise  $Q_n \approx 100$  el

Strips at larger radii (30, 37, 45, 52 cm)  
minimize material, cost

Pixels and strips provide primary pattern  
recognition capability

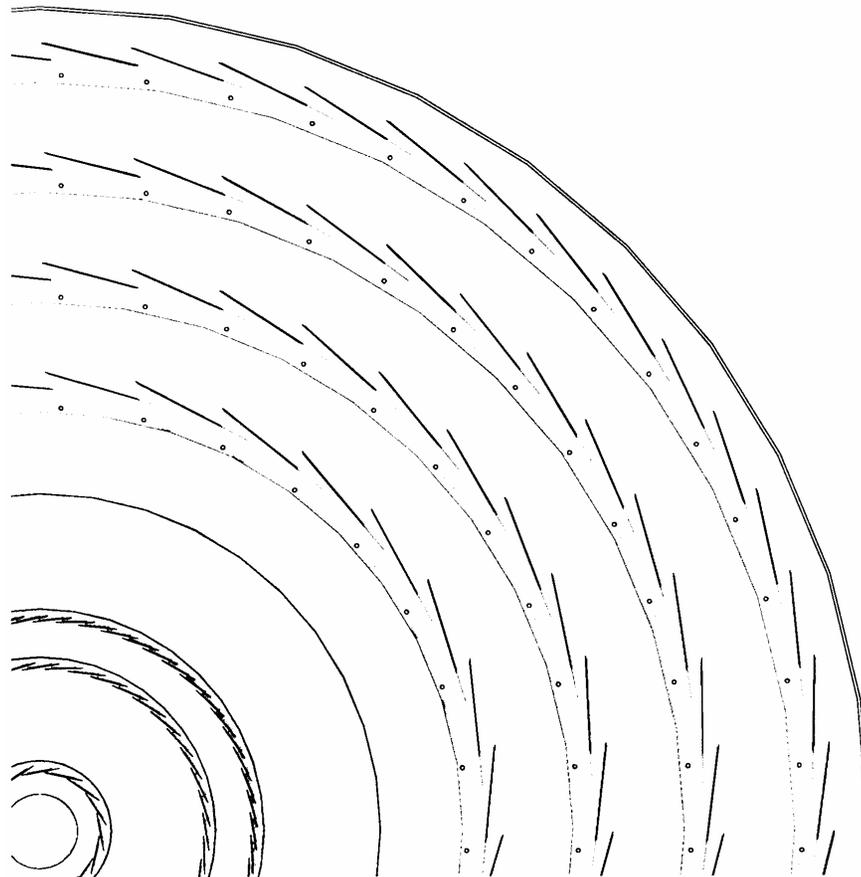
Straw drift chambers at outer radius (56 – 107 cm)

$\sim 70$  layers yield 40 space points at large  $R$  and  
augment pattern recognition by continuous  
tracking (least expensive solution)

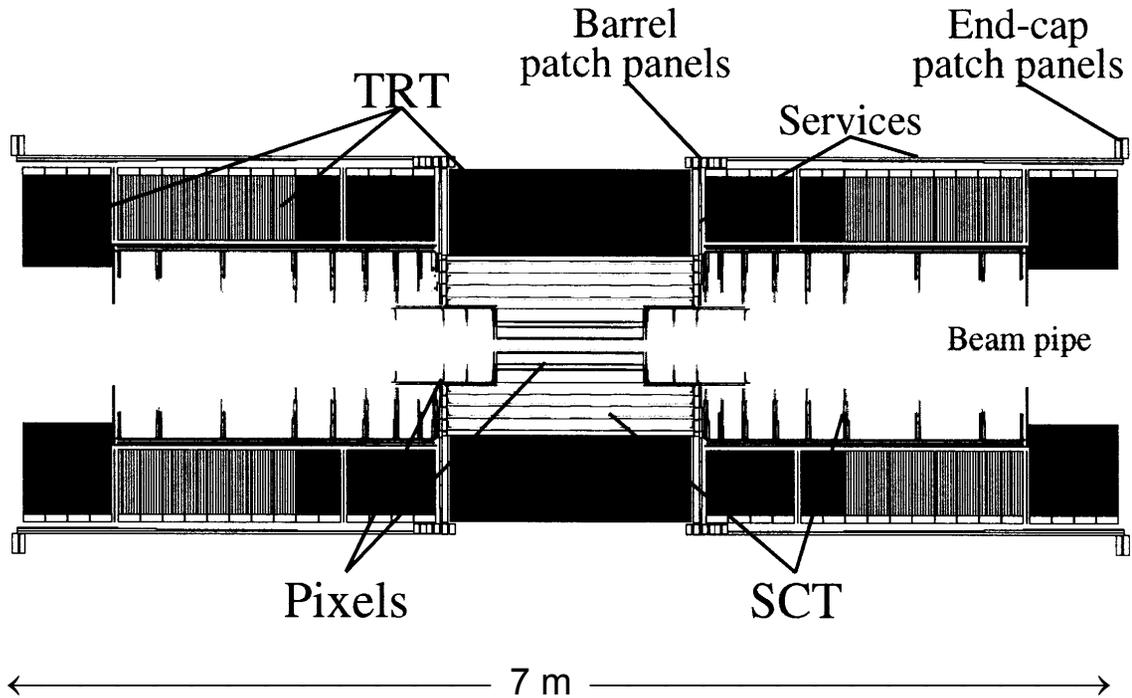


Detector modules arranged in cylindrical shells (barrels).

Modules are “shingled” to provide full coverage and overlap to facilitate relative position calibration.



Strip modules use back-to-back single-sided detectors with small-angle stereo (40 mrad) to provide z-resolution with negligible “ghosting”.



Resolution provided by  
3 detector types in barrel

	$r\phi$	$z$
Pixels	12 $\mu\text{m}$	66 $\mu\text{m}$
Strips	16 $\mu\text{m}$	580 $\mu\text{m}$
Straws	170 $\mu\text{m}$	—

Segmentation  $\Rightarrow$  Large number of data channels

Total number of channels and area:	Pixels	$1.4 \times 10^8$ channels	$2.3 \text{ m}^2$
	Strips	$6.2 \times 10^6$ channels	$61 \text{ m}^2$
	Straws	$4.2 \times 10^5$ channels	

But, only a small fraction of these channels are struck in a given crossing

Occupancy for pixels, $50 \mu\text{m} \times 300 \mu\text{m}$ :	4 cm Pixel Layer	$4.4 \times 10^{-4}$
	11 cm Pixel Layer	$0.6 \times 10^{-4}$

Occupancy for strip electrodes with $80 \mu\text{m}$ pitch, 12 cm length:	30 cm Strip Layer	$6.1 \times 10^{-3}$
	52 cm Strip Layer	$3.4 \times 10^{-3}$

Utilize local sparsification – i.e. on-chip circuitry that recognizes the presence of a hit and only reads out those channels that are struck.

$\Rightarrow$  data readout rate depends on hit rate, not on segmentation

First implemented in SVX chip

S.A. Kleinfelder, W.C. Carrithers, R.P. Ely, C. Haber, F. Kirsten, and H.G. Spieler, A Flexible 128 Channel Silicon Strip Detector Instrumentation Integrated Circuit with Sparse Data Readout, IEEE Trans. Nucl. Sci. **NS-35** (1988) 171

## Readout

Strips + Pixels: many channels

Essential to minimize

power

material (chip size, power cables, readout lines)

cost (chip size)

failure rate (use simple, well controlled circuitry)

Goal is to obtain adequate position resolution, rather than the best possible

⇒ Binary Readout

detect only presence of hits

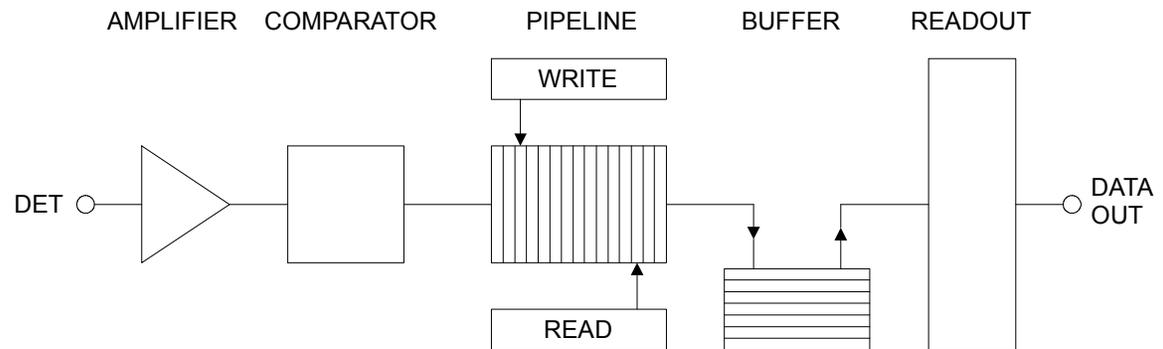
identify beam crossing

Architecture of ATLAS strip readout

Unlike LEP detectors ...

Crossing frequency  $\gg$   
readout rate

Data readout must proceed  
simultaneously with signal  
detection (equivalent to DC beam)

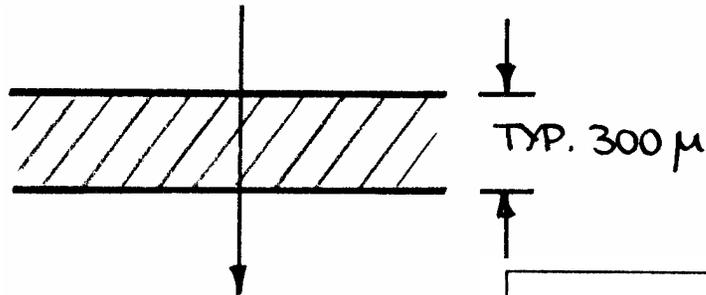


Single 128-channel BiCMOS chip (BJT + CMOS on same chip) in radiation-hard technology.

## Required Signal-to-Noise Ratio

Acceptable noise level established by signal level and noise occupancy

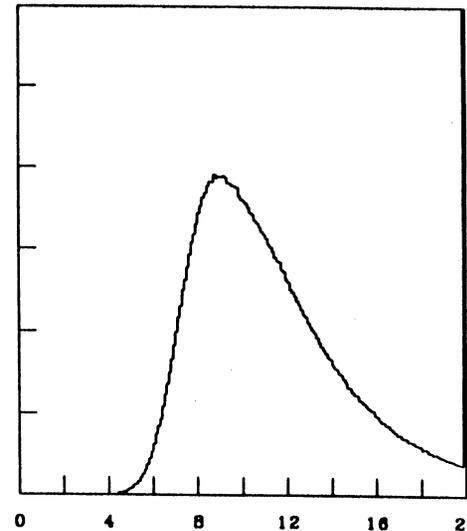
### 1. Signal Level



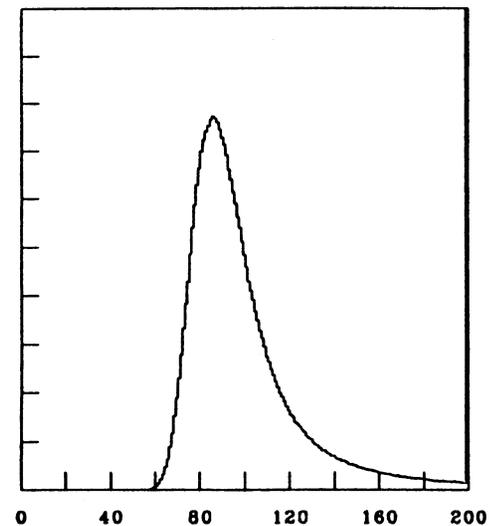
For minimum ionizing particles:  
 $Q_s = 22000 \text{ el (3.5 fC)}$

Signals vary event-by-event according to Landau distribution

Relative width of distribution decreases with increasing energy loss.



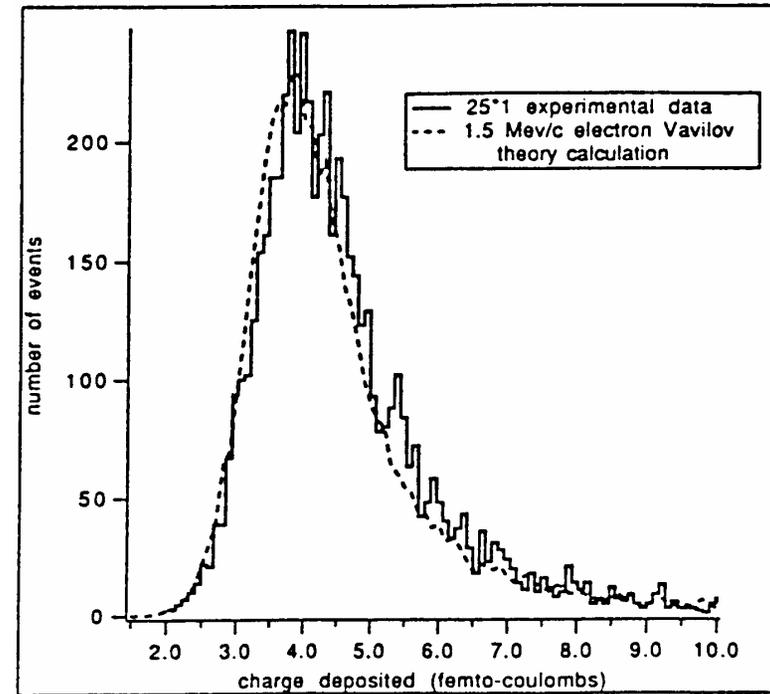
Si : 40  $\mu\text{m}$  thick



Si : 300  $\mu\text{m}$  thick  
 (calculation by G. Lynch)

Measured Landau distribution in a 300  $\mu\text{m}$  thick Si detector  
(Wood et al., Univ. Oklahoma)

The Landau distribution peaks at the most probable energy loss  $Q_0$  and extends down to about  $0.5 Q_0$  for 99% efficiency.



Assume that the minimum energy is  $f_L Q_0$ .

Tracks passing between two strips will deposit charge on both strips.

If the fraction of the signal to be detected is  $f_{sh}$ , the circuit must be sensitive signal as low as

$$Q_{\min} = f_{sh} f_L Q_0$$

## 2. Threshold Setting

It would be desirable to set the threshold much lower than  $Q_{min}$ , to be insensitive to threshold variations across the chip.

A lower limit is set by the need to suppress the noise rate to an acceptable level that still allows efficient pattern recognition.

As discussed in an Appendix, the threshold-to-noise ratio required for a desired noise rate  $f_n$  in a system with shaping time  $T_S$  is

$$\frac{Q_T}{Q_n} = \sqrt{-2 \log(4\sqrt{3}f_n T_S)}$$

Expressed in terms of occupancy  $P_n$  in a time interval  $\Delta t$

$$\frac{Q_T}{Q_n} = \sqrt{-2 \log\left(4\sqrt{3}T_S \frac{P_n}{\Delta t}\right)}$$

In the strip system the average hit occupancy is about  $5 \times 10^{-3}$  in a time interval of 25 ns. If we allow an occupancy of  $10^{-3}$  at a shaping time of 20 ns, this corresponds to

$$\frac{Q_T}{Q_n} = 3.2$$

The threshold uniformity is not perfect. The relevant measure is the threshold uniformity referred to the noise level. For a threshold variation  $\Delta Q_T$ , the required threshold-to-noise ratio becomes

$$\frac{Q_T}{Q_n} = \sqrt{-2 \log \left( 4\sqrt{3} T_S \frac{P_n}{\Delta t} \right)} + \frac{\Delta Q_T}{Q_n}$$

If  $\Delta Q_T / Q_n = 0.5$ , the required threshold-to-noise ratio becomes  $Q_T / Q_n = 3.7$ .

To maintain good timing, the signal must be above threshold by at least  $Q_n$ , so  $Q_T / Q_n > 4.7$ .

Combining the conditions for the threshold

$$\left( \frac{Q_T}{Q_n} \right)_{\min} Q_n \leq Q_{\min} \quad \text{and signal} \quad Q_{\min} = f_{sh} f_L Q_0$$

yields the required noise level

$$Q_n \leq \frac{f_{sh} f_L Q_0}{(Q_T / Q_n)_{\min}}$$

If charge sharing is negligible  $f_{sh} = 1$ , so with  $f_L = 0.5$ ,  $Q_0 = 3.5$  fC and  $(Q_T / Q_n)_{\min} = 4.7$

$$Q_n \leq 0.37 \text{ fC} \quad \text{or} \quad Q_n \leq 2300 \text{ el}$$

If the system is to operate with optimum position resolution, i.e. equal probability of 1- and 2-hit clusters, then  $f_{sh} = 0.5$  and

$$Q_n \leq 0.19 \text{ fC} \quad \text{or} \quad Q_n \leq 1150 \text{ el}$$

ATLAS requires  $Q_n \leq 1500 \text{ el}$ .

## Prototype Results

ATLAS has adopted a single chip implementation (ABCD chip).

- 128 ch, bondable to 50  $\mu\text{m}$  strip pitch
- bipolar transistor technology, rad-hard
  - ⇒ minimum noise independent of shaping time
- peaking time:  $\sim 20$  ns (equivalent CR-RC<sup>4</sup>)
- double-pulse resolution (4 fC – 4 fC): 50 ns
- noise, timing: following slides
- 1.3 to 1.8 mW/ch (current in input transistor adjustable)
- on-chip DACs to control threshold + operating point
- Trim DACs on each channel to reduce channel-to-channel gain and threshold non-uniformity
- Readout allows defective chips to be bypassed
- Optical fiber readout with redundancy
- die size: 6.4 x 4.5 mm<sup>2</sup>

For illustration, the following slides show data from a previous prototype IC, the CAFE chip

This was part of an initial 2-chip implementation  
(BJT analog chip and CMOS digital chip)

Production ICs are single chip BiCMOS with same architecture: similar results

## CAFE Timing Performance

1. Chips from run 1 measured on test boards

- irradiated to  $10^{14} \text{ cm}^{-2}$  (MIP equiv)

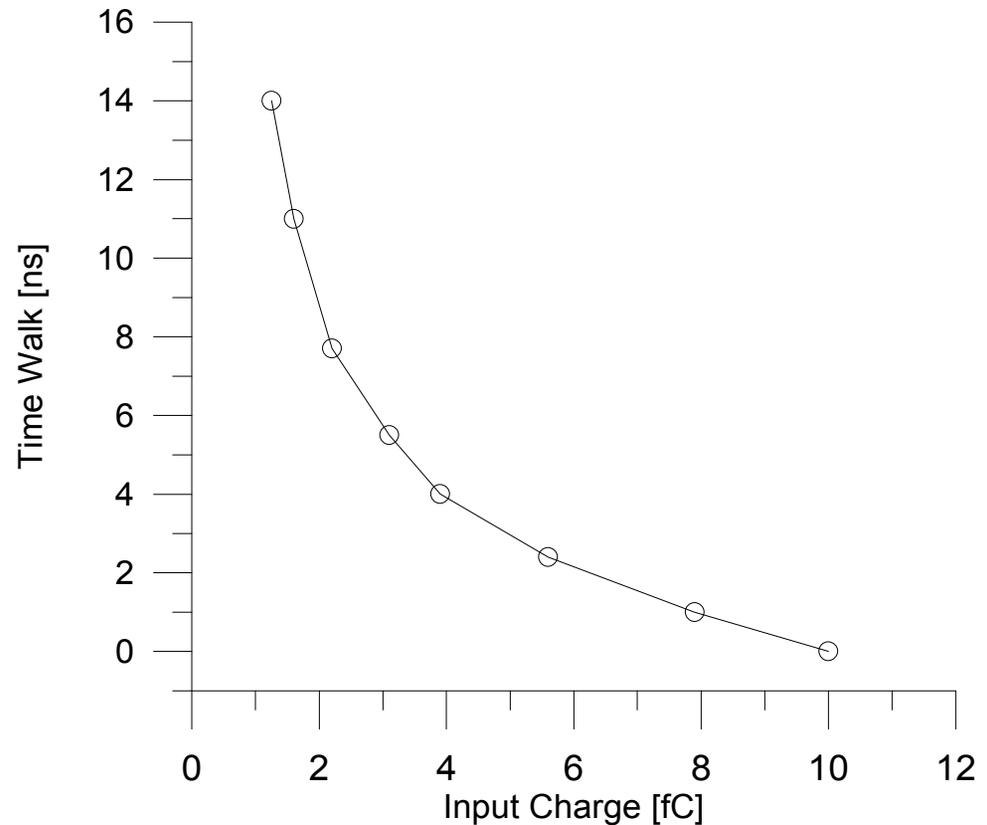
Time Walk	1.25 - 10 fC:	16 ns
1 fC threshold	1.25 - 4 fC:	12 ns
	4 fC - 10 fC:	4 ns

Jitter at 1.25 fC  $\approx$  4 ns FWHM

Total time diistribution (99% efficiency)  
confined within about 18 ns.

2. Chips from Run 2 measured on test  
boards (**pre-rad**)

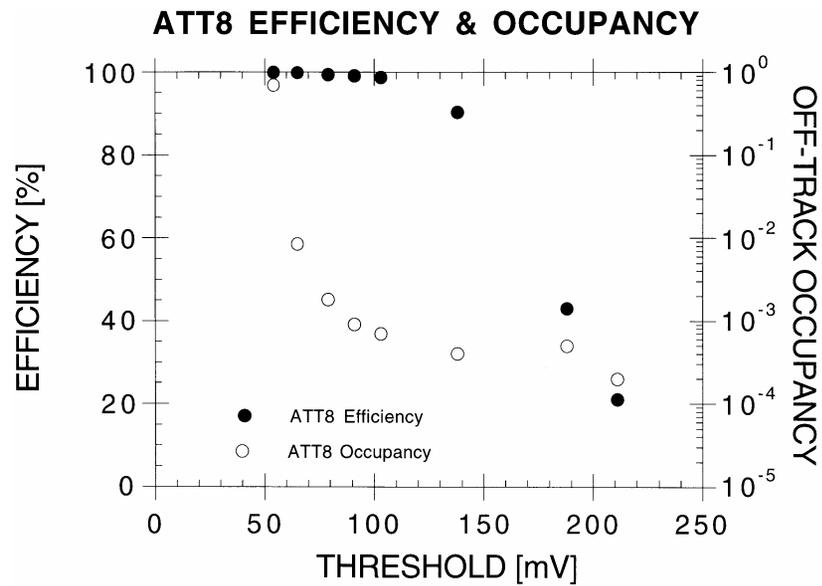
$C_{\text{load}} = 15 \text{ pF}$ , 1 fC threshold, jitter as  
above



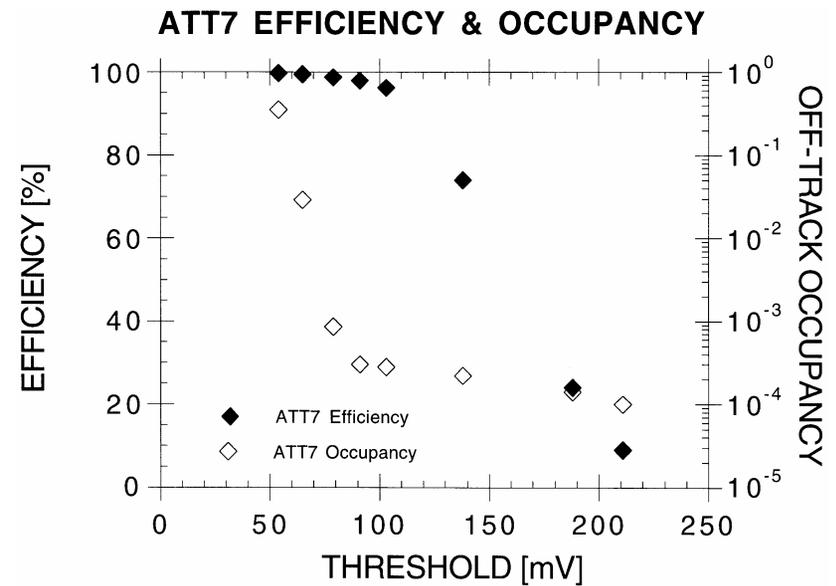
## Test Beam Data

### Tracking Efficiency vs. Occupancy for Full-Length Modules

non-irradiated module



irradiated module ( $\Phi = 10^{14} \text{ cm}^{-2}$ )



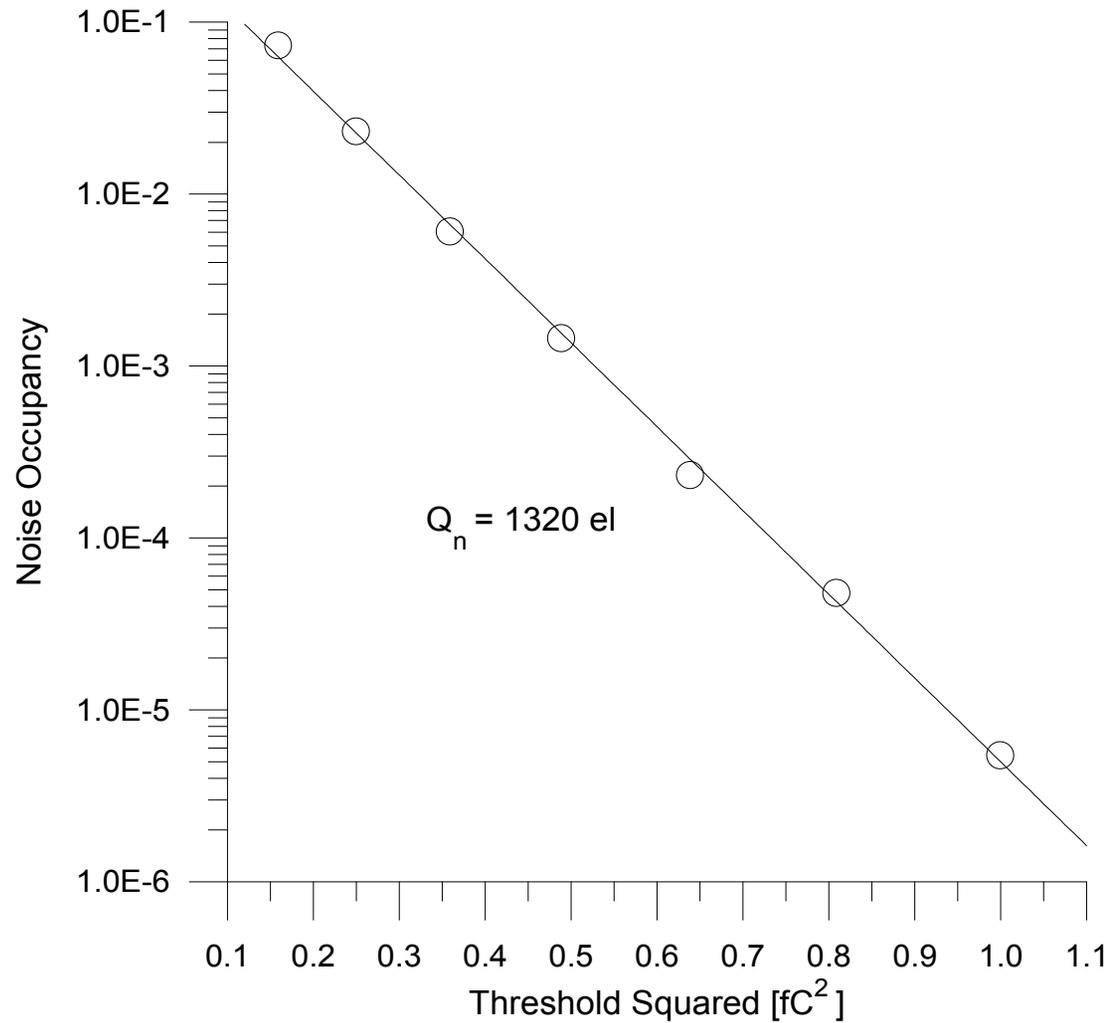
## Noise Occupancy vs. Threshold

Module with CAFE chip in test beam position at KEK

Baseline fluctuations, digital cross-talk

⇒ deviations from straight line plot (gaussian noise)

test beam noise same as measured in laboratory (within 5% simulation)



## ATLAS Silicon Strip Detector Module (mounted in fabrication fixture)

Two  $6 \times 6 \text{ cm}^2$  single-sided Si strip detectors butted edge-to-edge to form 12 cm long detector

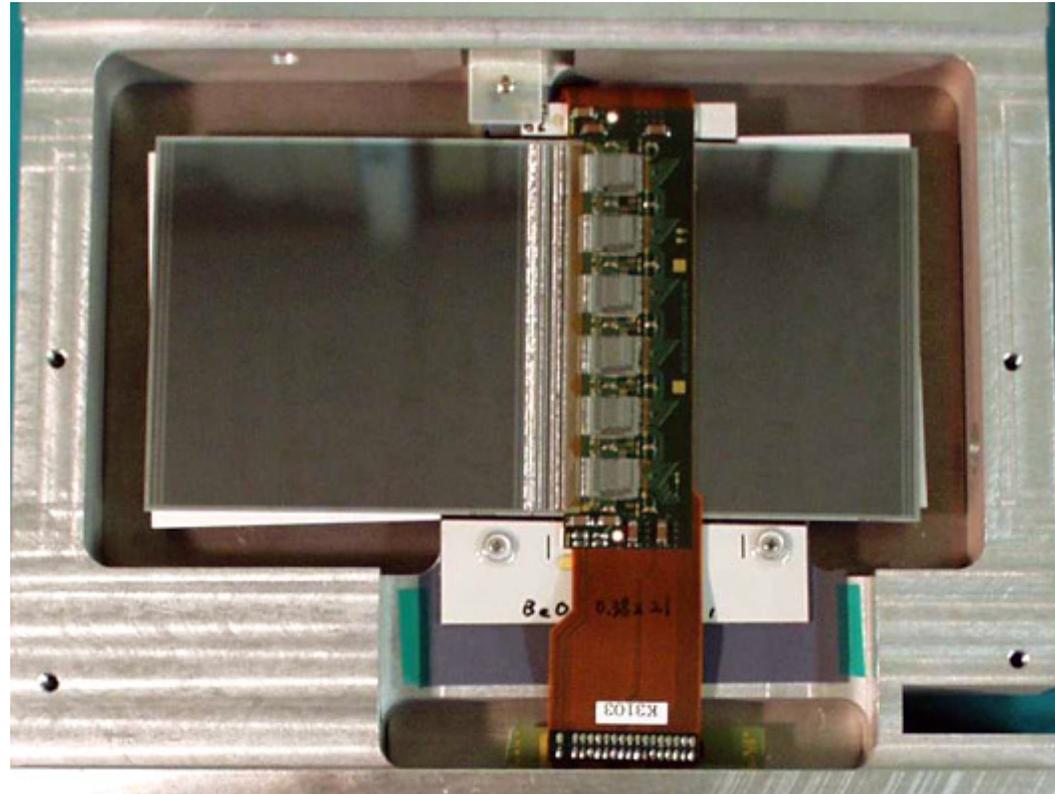
Two  $6 \times 12 \text{ cm}^2$  detectors glued back-to-back and rotated to one another by 40 mrad to form small-angle stereo

Readout ICs – 128 channels each – mounted on detectors and connected at middle (reduce thermal noise of strip electrode resistance).

Strip pitch:  $80 \mu\text{m}$   
no. of channels:  $2 \times 768$

Binary readout with on-chip pipeline and readout sparsification

Kapton pigtail connects to local opto-module for clock, control, data transmission



## Two-Dimensional Detectors

Example: Crossed strips on opposite sides of Si wafer

$n$  readout channels  $\Rightarrow n^2$  resolution elements

Problem: ambiguities with multiple hits

$n$  hits in acceptance field  $\Rightarrow$

$n$   $x$ -coordinates and  $n$   $y$ -coordinates

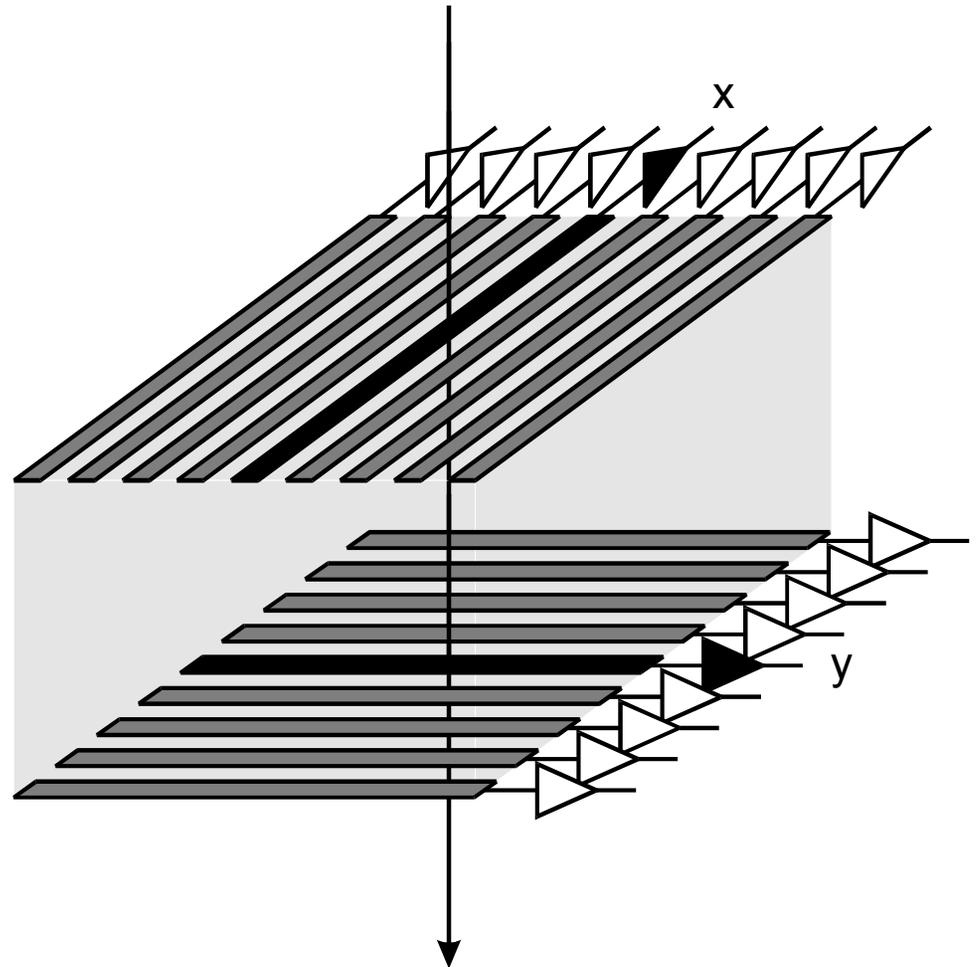
$\Rightarrow n^2$  combinations

of which  $n^2 - n$  are “ghosts”

ATLAS strips reduce ambiguities by using small angle stereo (40 mrad).

Not sufficient at small radii –

need non-projective 2D detector



## Pixel Detectors with Random Access Readout (K. Einsweiler et al.)

“Smart Pixels”

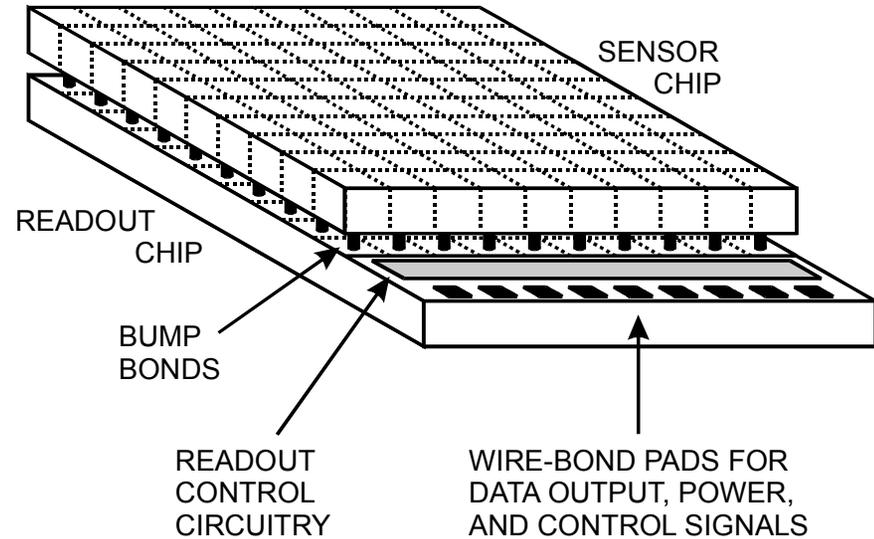
Quiescent state:

no clocks or switching in pixel array

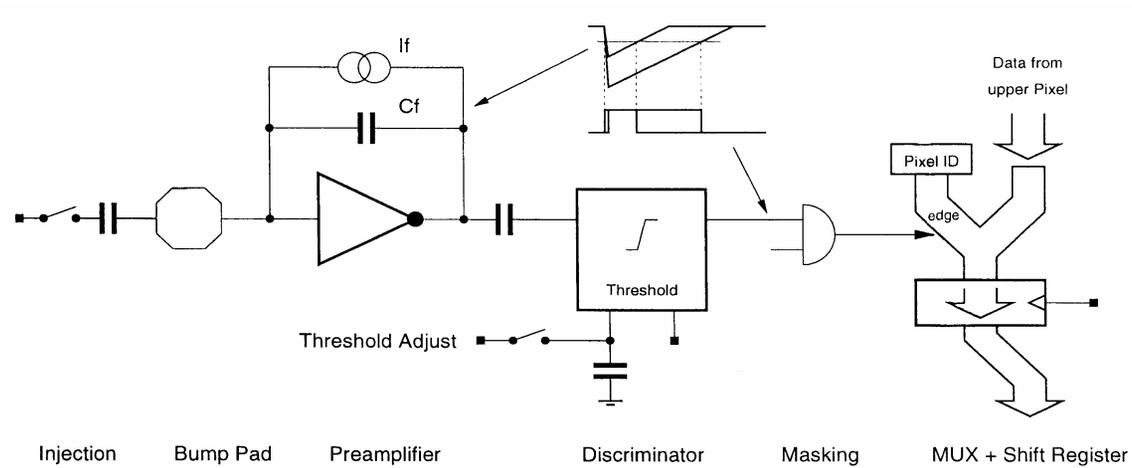
Pixel circuitry only issues signals when struck.

Struck pixels send address + time stamp  
to peripheral register

On receipt of trigger selectively read out pixels.



## Block Diagram of Pixel Cell



- Q-amplifier + shaper per pixel
- threshold comparator per pixel
- trim-DAC per pixel for fine adjustment of threshold
- time-over-threshold analog digitization
- test pulse per pixel
- bad pixels can be masked

Pixel size:  $50 \mu\text{m} \times 400 \mu\text{m}$

size historical:  
could be  
 $50 \mu\text{m} \times 200 \mu\text{m}$

Power per pixel:  $< 40 \mu\text{W}$

Final chip: 18 columns x 160 pixels  
(2880 pixels)

Module size:  $16.4 \times 60.4 \text{ mm}^2$

16 front-end chips per module

46080 pixels per module

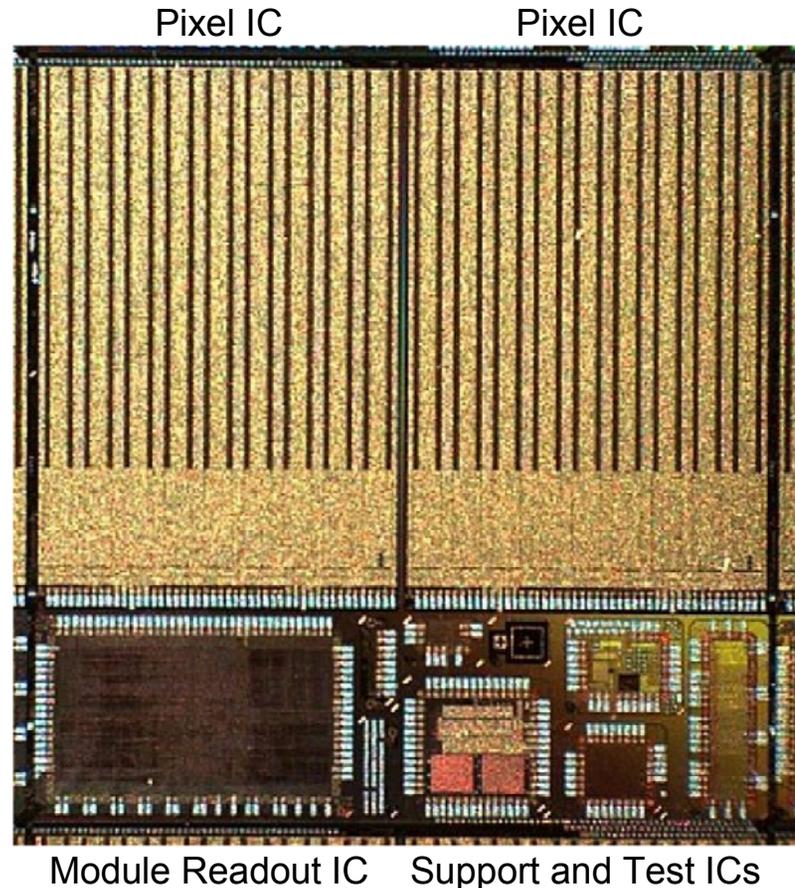
fabricated in  $0.25 \mu\text{m}$  CMOS

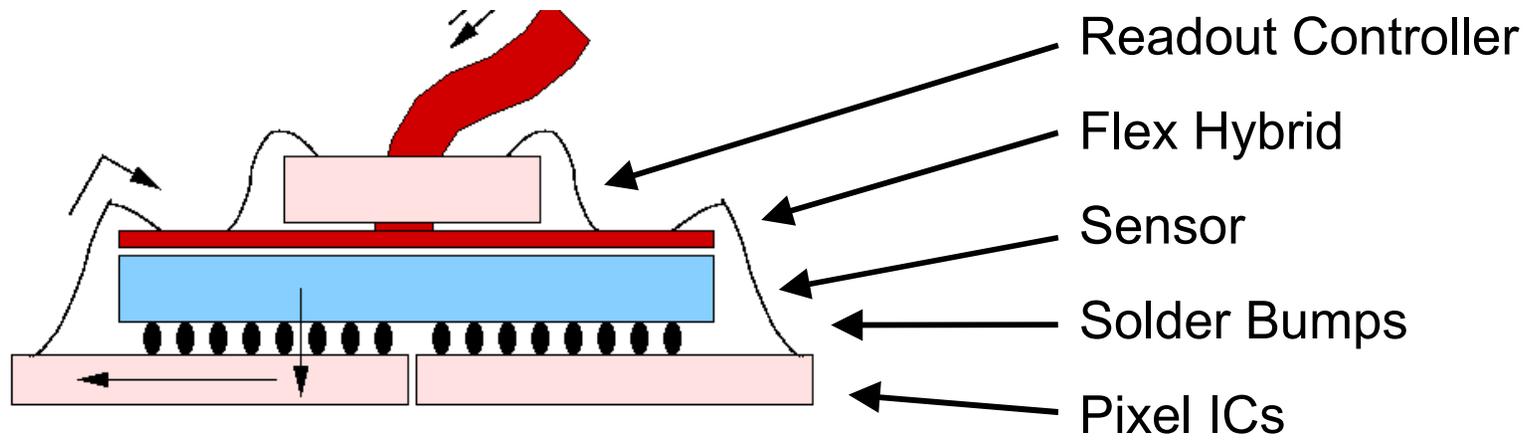
$\sim 3.5 \cdot 10^6$  transistors

functional to  $> 100 \text{ Mrad}$

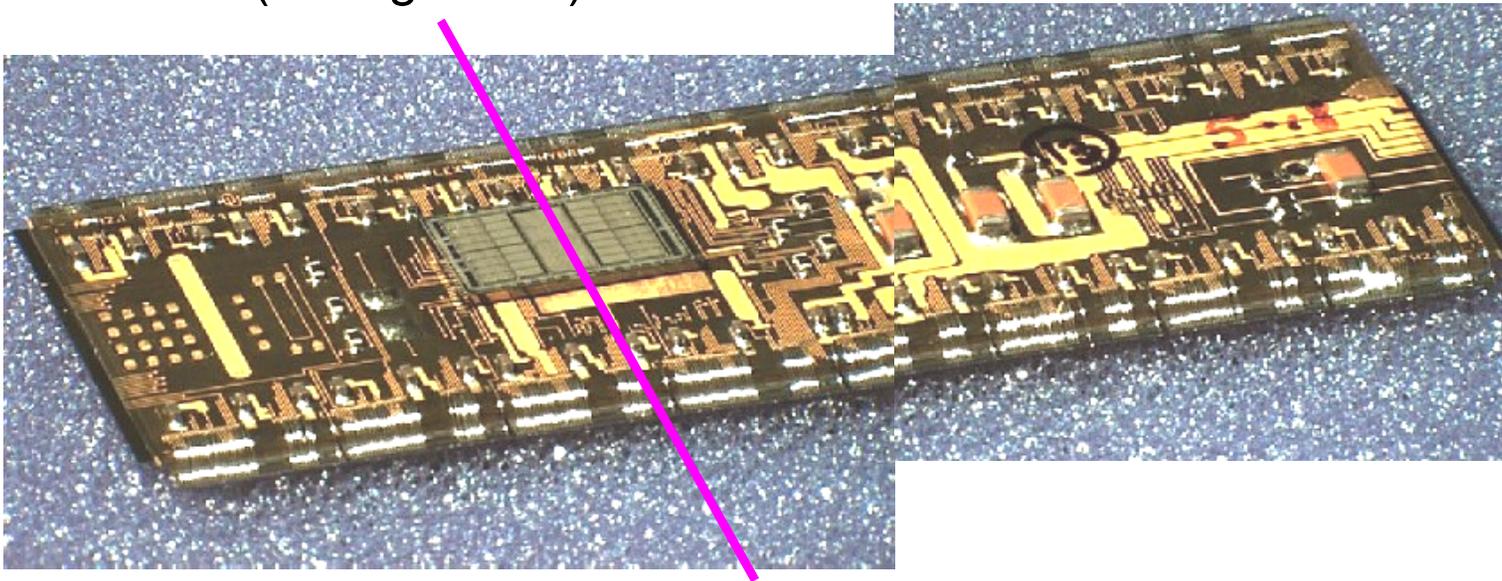
Measured noise level:  $\sim 100 \text{ e}$  (threshold  $<$  noise)

Radiation resistant to higher fluences than strips because  
low noise provides large performance reserves.



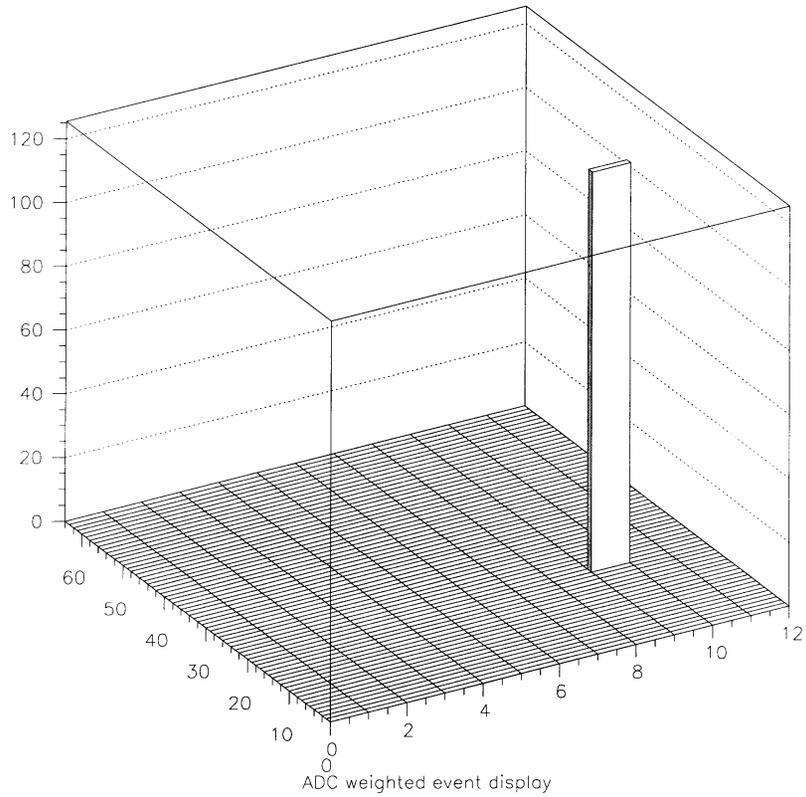


Schematic Cross Section  
(through here)

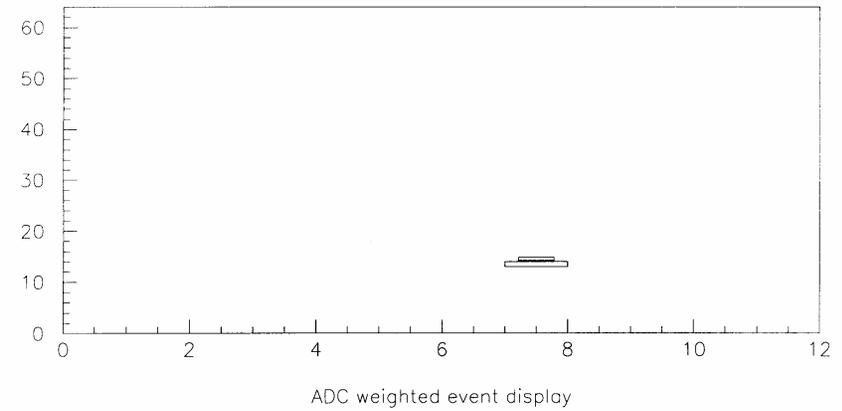
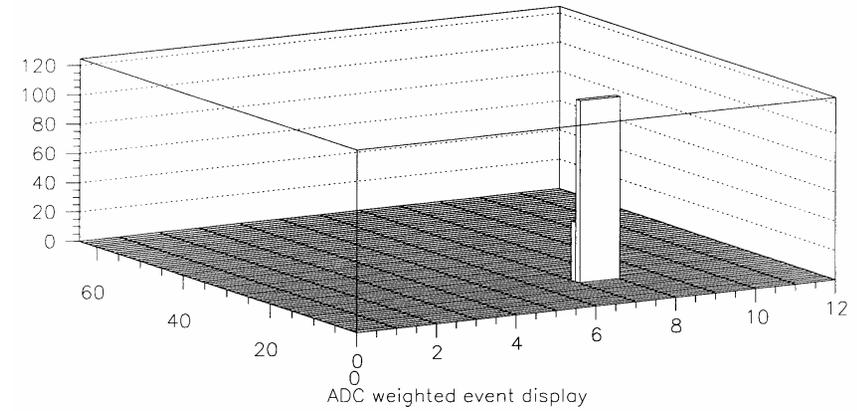


## Test Beam Results

### Track through single pixel



### Charge sharing



## Advantages of pixels at LHC

2D segmentation

⇒ Pattern recognition at small radii

Low capacitance

⇒ high S/N

⇒ allows degradation of both detector signal and electronic noise due to radiation damage

small detector elements

⇒ detector bias current per element still small after radiation damage

Drawback:

Engineering complexity order of magnitude greater than previous chips

Question: What is the ultimate limit of radiation resistance?

Current design could survive 5 – 10 years at nominal LHC luminosity.

Luminosity upgrade? Much R&D necessary.